

## Poster Presentation

Poster Number	Presenter	Position	Affiliation	Title	Authors
P-01	Kazuaki Kurihara	Toshiba Corporation, Japan	Senior Research Scientist	Study of Plasma Nitridation of Silicon under Identified Reactive Species Irradiation in a Nitrogen Plasma	Kazuaki Kurihara
P-02	Kazuki Denpoh	Tokyo Electron AT Ltd., Japan	Senior Engineer	Locally Enhanced Discharges at Gas Hole Outlets of Showerhead in a Plasma Etch Reactor	Kazuki Denpoh
P-03	Jinsu Park	Myongji University, Korea	Student	Statistical Analysis of Emission Intensity for Generated Oxygen Plasma using Optical Emission Spectroscopy	Jinsu Park and Sang Jeen Hong
P-04	Tetsuya Tatsumi	Sony Corporation, Japan	Distinguished Researcher	Control of Damage on Si-sub. during Gate Etching	T. Tatsumi, T. Ohchi, S. Kobayashi, T. Takizawa and S. Hamaguchi
P-05	Ryota Sasaki	Tokyo Institute of Technology, Japan	Student	Atomospheric Large Sized Pulse/RF Remote Plasma Source for Surface Treatment	Ryota Sasaki, Wataru Kumagai, Hidekazu Miyahara, Eiki Hotta and Akitoshi Okino
P-06	Butsurin Jinnai	Tohoku University, Japan	Student	Effects of Photon Irradiation during Plasma Etching Processes for Low-k films	Butsurin Jinnai and Seiji Samukawa
P-07	Masahiro Yonemoto	Tohoku University, Japan	Student	Fabrication of Sub-10 nm Vertical Nanocolumn Structure by using Defect-free Neutral Beam Etching	Masahiro Yonemoto and Seiji Samukawa
P-08	Aiko Sato	Tohoku University, Japan	Researcher	Chamber Cleaning for Chemical Vapor Deposition using Pulse Time Modulated F2 Gas Plasma	A. Sato, Y. Hoshino, T. Ozaki, M. Kondo and S. Samukawa
P-09	Yasuo Murakami	Osaka University / Canon Anelva, Japan	Senior Engineer	Molecular Dynamics Simulation of Carbon Thin Film Deposition Processes	Yasuo Murakami, Seishi Horiguchi and Satoshi Hamaguchi
P-10	Kazuhiro Karahashi	Osaka University, Japan	Assistant Professor	Surface Reactions of SiO <sub>2</sub> and Si Etching by CF <sub>3</sub> <sup>+</sup> Ions	Kazuhiro Karahashi and Satoshi Hamaguchi
P-11	Ayuta Suzuki	Osaka University, Japan	Student	Atomic-scale Numerical Simulations of SiOCH Film Etching Processes by Energetic CF <sub>3</sub> Beams	Ayuta Suzuki, Toshifumi Takizawa, Michiro Isobe and Satoshi Hamaguchi
P-12	Ayumi Ando	Osaka University, Japan	Postdoctoral Research Fellow	CH <sub>4</sub> /Ar Plasma Measurements with Terahertz Time-domain Spectroscopy	Ayumi Ando, Tomoko Kurose, Katsuhisa Kitano, Hideaki Kitahara, Keisuke Takano, Masahiko Tani, Masanori Hangyo and Satoshi Hamaguchi
P-13	Tsunehiro Maehara	Ehime University, Japan	Associate Professor	Generation of Hydrogen Peroxide by RF Plasma in Water	Tsunehiro Maehara, Ippei Miyamoto, Atsushi Iwamae, Hiroshi Yamashita, Shinobu Mukasa, Hiromichi Toyota, Sinfuku Nomura and Ayato Kawashima
P-14	Hyunwoo Lee	Pohang University of Science and Technology,	Student	Modelings of Atmospheric Pressure Plasmas	Hyunwoo Lee, Yongjun Hong, Ganyoung Park and Jaekoo Lee
P-15	Keiicho Urabe	Kyoto University, Japan	Student	Spatiotemporally Resolved Spectroscopic Diagnostics of Low-frequency Driven Microplasma Jet	Keiichiro Urabe, Yosuke Ito, Makoto Kubo and Kunihide Tachibana
P-16	Teruki Naito	Kyoto University, Japan	Student	Diagnostics of Microplasma Parameters by Arranging Periodic Structures of Microplasmas	Teruki Naito, Takuya Shimomura, Osamu Sakai and Kunihide Tachibana
P-17	Tatsuru Shirafuji	Kyoto University, Japan	Associate Professor	Electrical Discharges in Microbubbles formed by Water Electrolysis on <i>Fabric</i> Electrodes	Masaru Kimura, Osamu Sakai, Tatsuru Shirafuji and Kunihide Tachibana
P-18	Tsuyohito Ito	Osaka University, Japan	Associate Professor	Optical Diagnostics of the Electron Temperature and Density in an Ar DC Glow Discharge Plasma	Tsuyohito Ito, Tomoya Tamura and Satoshi Hamaguchi
P-19	Takashi Yoshida	Osaka University, Japan	Inviting Reseacher	Development of RF Atmospheric Plasma Generator and Application to NO <sub>x</sub> Reduction	Takashi Yoshida, Takayoshi Yumii and Noriaki Kimura
P-20	Takamichi Hirata	Musashi Institute of Technology, Japan	Associate Professor	Chemical Modification of CNT-Based Bio-Nanosensor by Plasma-Activation	Takamichi Hirata, Shoji Amiya and Masahiro Akiya
P-21	Akira Wada	Tohoku University, Japan	Student	Damage-free Surface Modification of Carbon Nanotubes using Advanced Neutral Beam	Akira Wada, Yoshinori Sato, Masahiko Ishida, Fumiyuki Nihey, Kazuyuki Tohji and Seiji Samukawa
P-22	Chi-Hsien Huang	Tohoku University, Japan	Postdoctoral Researcher	Fabrication of Nanodisk by Defect-free Chlorine Neutral Beams and its Quantum Effect Measurement	C.-H. Huang, M. Igarashi and S. Samukawa
P-23	Shunsuke Kuroda	Tohoku University, Japan	Student	Pressure Dependence of Single-walled Carbon Nanotube Growth with Diffusion Plasma CVD	S.Kuroda, T.Kato and R.Hatakeyama
P-24	Yohei Hanabusa	Tohoku University, Japan	Student	Encapsulation of Ionic Fullerenes into Single-Walled Carbon Nanotubes using Plasma Ion Irradiation Method	Yohei Hanabusa, Toshiro Kaneko, Shohei Nisigaki and Rikizo Hatakeyama